

Customer No. 22,852  
Attorney Docket No. 02887.0259

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

O / P  
MAR 25 2004  
PATENT & TRADEMARK OFFICE  
In re Application of: )  
Junji SUGAMOTO et al. )  
Application No.: 10/706,090 ) Group Art Unit: 2812  
Filed: November 13, 2003 ) Examiner:  
For: SEMICONDUCTOR WAFER )  
TREATMENT METHOD, )  
SEMICONDUCTOR WAFER )  
INSPECTION METHOD, )  
SEMICONDUCTOR DEVICE )  
DEVELOPMENT METHOD )  
AND SEMICONDUCTOR )  
WAFER TREATMENT )  
APPARATUS )

**MAIL STOP MISSING PARTS**  
**Commissioner for Patents**  
**P.O. Box 1450**  
**Alexandria, VA 22313-1450**

Sir:

**INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)**

Pursuant to 37 C.F.R. §§1.56 and 1.97(b), applicants bring to the Examiner's attention the documents listed on attached Form PTO-1449. Copies of the listed documents are attached. Applicants respectfully request that the Examiner consider the documents listed on attached Form PTO-1449 and indicate that they were considered by making an appropriate notation on this form.

This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits for the above-referenced application.

The following is a concise statement of relevance of the non-English language documents:

1. Japanese Patent Laid Open (Kokai) No. 11-054579 discloses a method of inspecting and evaluating the BMD (Bulk Micro Defect) in semiconductor substrates. BMD is changed to pit shape by HF cleaning. Etch pit density on the whole wafer is measured by particle counter by laser scattering method. (Fig. 1 and lines 26-42 of left portion of page 3). The relevance of this document is also discussed at page 2 of the specification of the present application, and an English-language abstract of this document is also enclosed.
2. Japanese Patent Laid Open (Kokai) No. 08-191090 discloses a method of inspecting and evaluating the crystal defects and contaminations on the whole surface of semiconductor substrates. Adsorbing the radioactive isotope to defects, the defect distribution is measured by computed radiography. (Fig. 1 and lines 44-50 of right portion of page 3 and lines 1-6 of left portion of page 4). The relevance of this document is also discussed at page 2 of the specification of the present application, and an English-language abstract of this document is also enclosed.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicants determine that the cited documents do not constitute "prior art" under United States law, applicants reserve the right to present to the Office the relevant facts and law regarding the

Customer No. 22,852  
Attorney Docket No. 02887.0259

appropriate status of such documents. Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

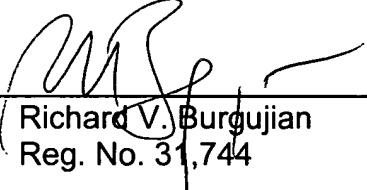
If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,  
GARRETT & DUNNER, L.L.P.

Dated: March 25, 2004

By:

  
Richard V. Burgujian  
Reg. No. 31,744

Enclosures  
RVB/FPD/gah

## INFORMATION DISCLOSURE CITATION

Atty. Docket No. 02887.0259		Application 10/706,090 No.	
Applicant Junji SUGAMOTO et al.			
Filing Date	November 13, 2003 Group: 2812		

## U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
01						

## FOREIGN PATENT DOCUMENTS

	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
	11-54579	02/26/1999	Japan			Abstract
	08-191090	07/23/1996	Japan			Abstract

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)


Examiner	Date Considered
<p>*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>	
Form PTO 1449	Patent and Trademark Office - U.S. Department of Commerce